

Supporting Information

EUV Photofragmentation Study of Hybrid Nonchemically Amplified Resists Containing Antimony as Absorption Enhancer

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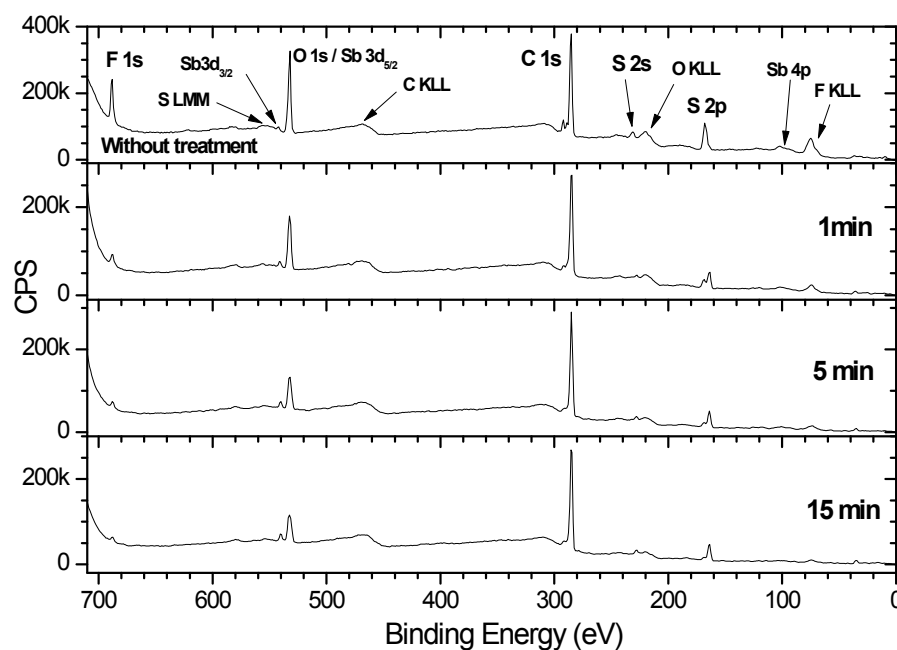


Figure S1. XPS wide scan spectra of pristine hybrid non-CAR resist 2.15%-MAPDSA-MAPDST thin film and irradiated at 103.5 eV for 1, 5 and 15 min.

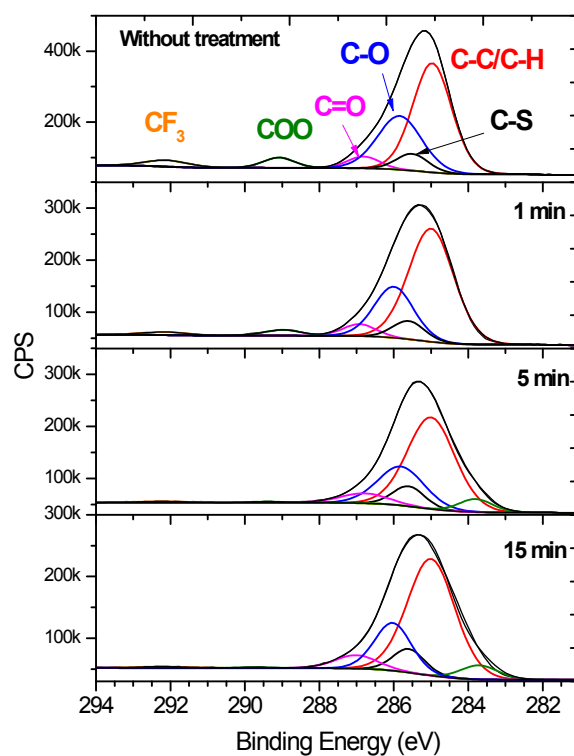


Figure S2. High-resolution XPS spectra of the C 1s envelope of pristine hybrid non-CAR resist 2.15%-MAPDSA-MAPDST thin film and irradiated at 103.5 eV for 1, 5 and 15 min.

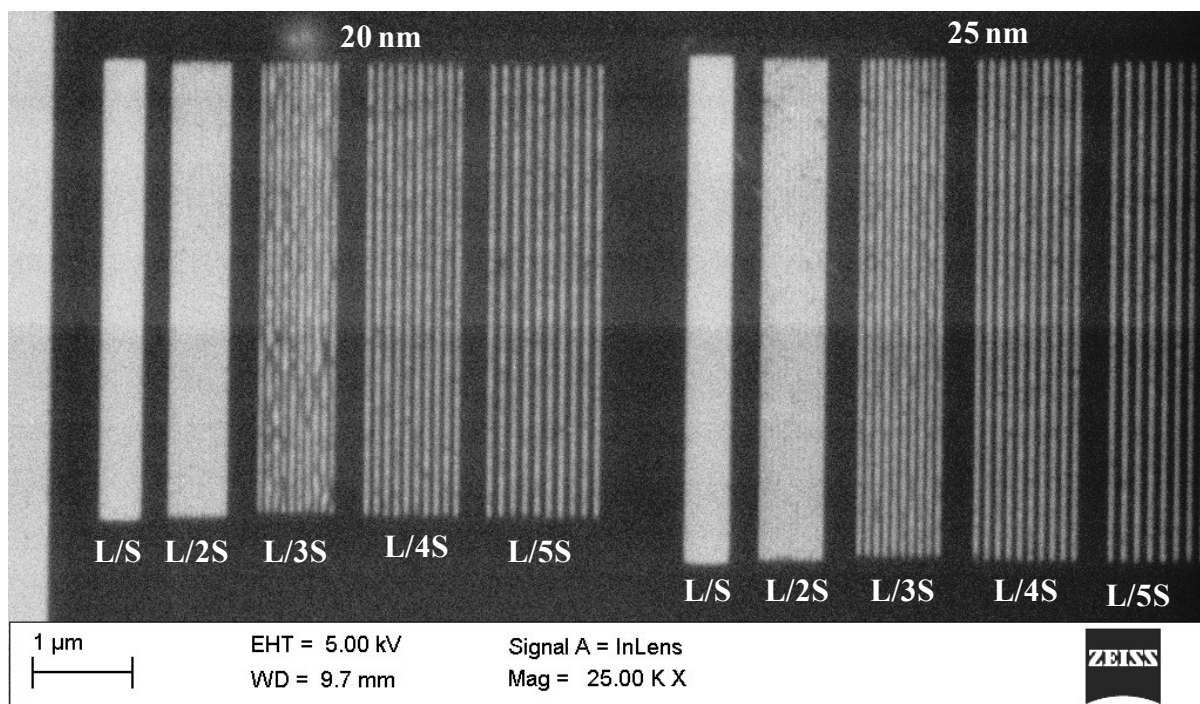


Figure S3. SEM image of EUVL patterned 20 and 25 nm (L/S to L/5S) line patterns of 2.15%-MAPDSA-MAPDST resist at the dose $\sim 22 \text{ mJ/cm}^2$.